

Supporting Information

Application of downshifting and antireflection stacked layers synthesized using a wet chemistry method with broad UV excitation for silicon heterojunction solar cells

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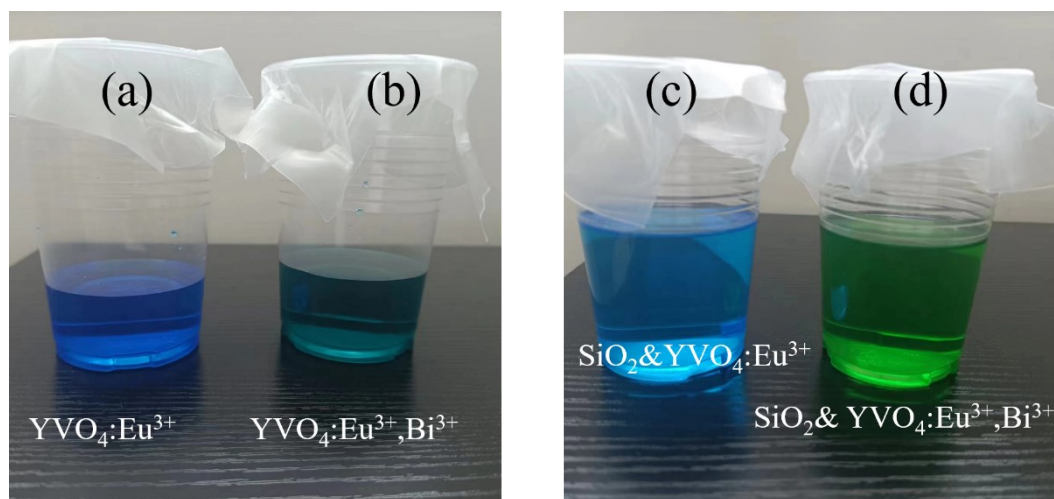


Figure S1. (a)YVO₄:Eu³⁺, (b) and YVO₄:Eu³⁺, Bi³⁺, (c) SiO₂ and YVO₄:Eu³⁺, (d)SiO₂ and YVO₄:Eu³⁺, Bi³⁺.

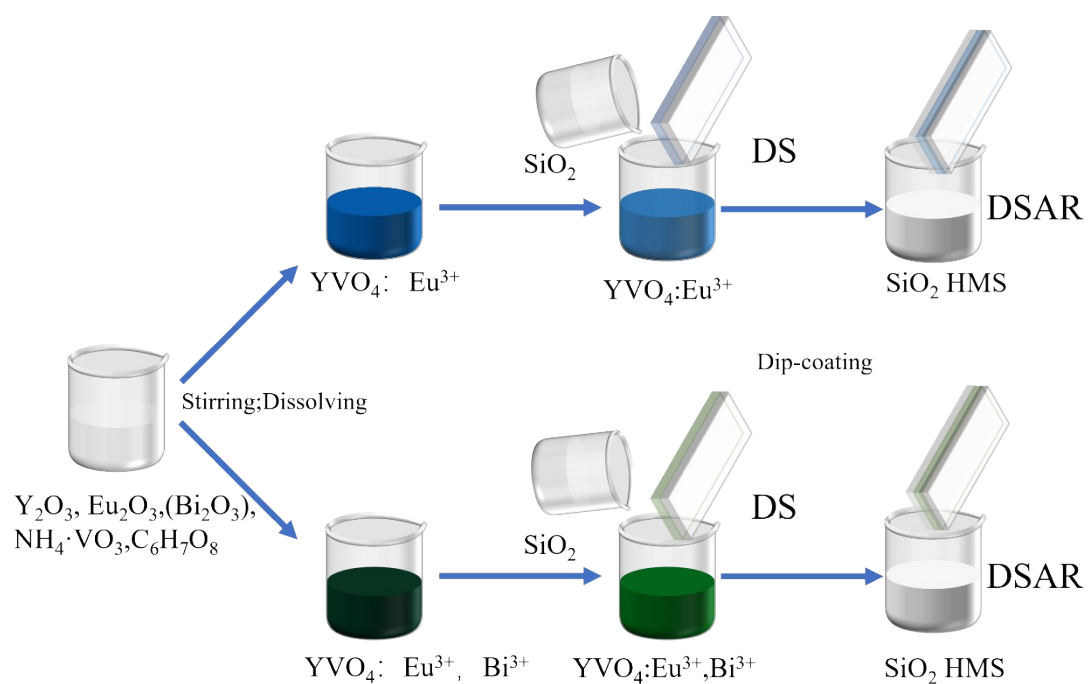


Figure S2. The process flow diagram of the DS and DSAR.

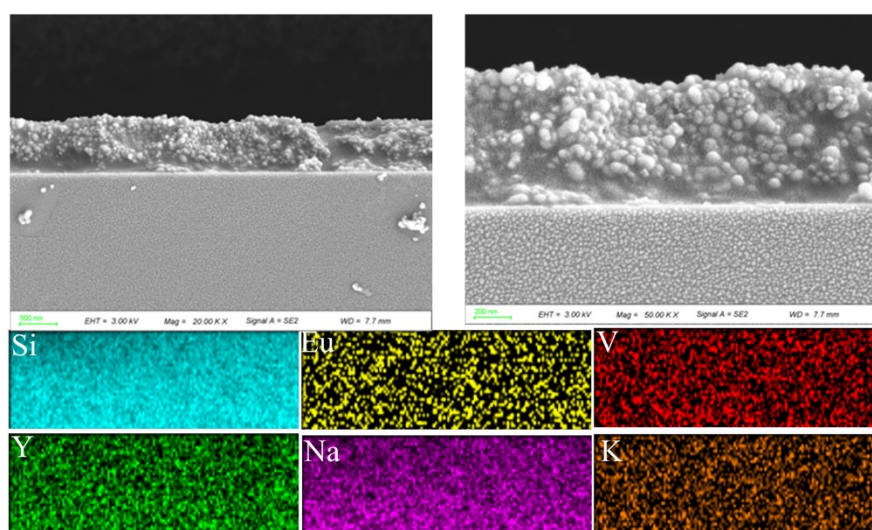


Figure S3. SEM cross-sectional image and EDS spectrum analysis of YVO₄:Eu³⁺.

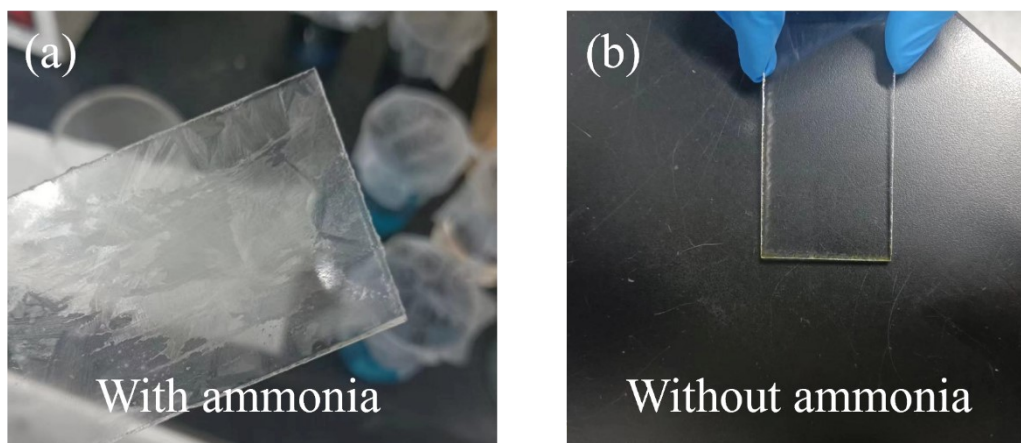


Figure S4. (a) Film surface with ammonia. (b) Film surface without ammonia.

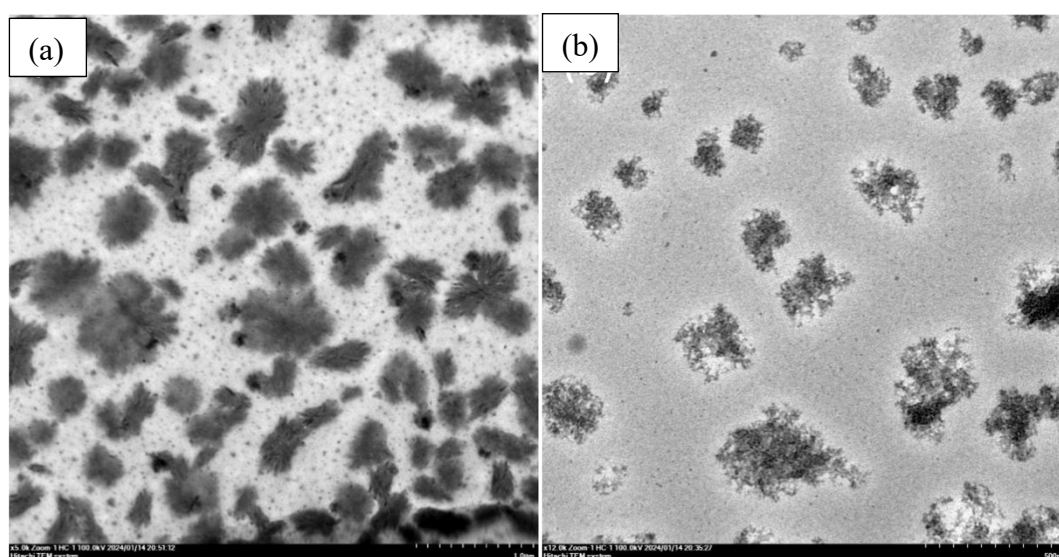


Figure S5: (a) TEM images of YVO₄:Eu³⁺, Bi³⁺. (b) SiO₂ and YVO₄:Eu³⁺, Bi³⁺.